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Application/Co	ontrol No.	Applicant(s)/P Reexamination		
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Examiner		Art Unit		_
W. David Cole	eman	2823		

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SEARCH NOT (INCLUDING SEARCH)
	DATE	EXMR
EAST 2.0.1 USPGPUBS; USPAT; JPO; EPO; Derwent; IBMTDB; IEEE; see search notes.		
Applicant clains an interconnect with a diffusion barrier formed after a lateral etching process.		
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